

## Approaching the Mott-Hubbard insulator in the 85-K superconductor $\text{Bi}_2(\text{Sr}, \text{Ca})_3\text{Cu}_2\text{O}_{8+d}$ by doping with Tm

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As  $x$  increases in  $\text{Bi}_4\text{Sr}_3\text{Ca}_{3-x}\text{Tm}_x\text{Cu}_4\text{O}_{16+y}$  the Hall carrier density  $n_H$  decreases linearly. The variation is consistent with Mott-Hubbard behavior, but in conflict with band-structure results which ignore correlations. We find that the variation of  $T_c$  vs  $n_H$  is nonmonotonic. The source of the large carrier population (0.4/Cu) in the undoped ( $x=0$ ) compound is discussed.

The recently discovered superconductors based on Bi-Sr-Ca-Cu-O strongly resemble  $\text{YBa}_2\text{Cu}_3\text{O}_7$  (called 1:2:3) and  $\text{La}_{2-x}\text{Sr}_x\text{CuO}_4$  (2:1:4) in structure.<sup>1-4</sup> In particular, the  $N=2$  member  $\text{Bi}_2(\text{Sr}, \text{Ca})_3\text{Cu}_2\text{O}_{8+d}$  (2:2:1:2), which has a transition temperature  $T_c$  near 85 K, is similar to the 1:2:3 structure, with the Bi-O bilayer replacing the Cu(1) chains ( $N$  is the number of adjacent  $\text{CuO}_2$  planes). The structural similarity raises a number of interesting questions on the variation of  $T_c$  and the carrier density  $n$  as the chemical potential  $\mu$  is raised by chemical doping. If strong correlation (large  $U$ ) exists in the Bi compound the behavior of  $n$  vs  $\mu$  should imitate the behavior found in the 2:1:4 and 1:2:3 systems.<sup>5-8</sup> On the other hand, if  $U$  is negligible, band-structure calculations should give a satisfactory account of the variation of  $n$  vs  $\mu$ . A second question concerns the role of the Bi-O planes. Band-structure calculations,<sup>9,10</sup> which ignore correlations, indicate that a band associated with Bi-O intersects the Fermi level. This raises the important issue of whether the superconducting carriers also exist in the Bi-O planes.

To address these questions we have performed Hall and resistivity measurements on a series of well-characterized polycrystalline samples of  $\text{Bi}_4\text{Sr}_3\text{Ca}_{3-x}\text{Tm}_x\text{Cu}_4\text{O}_{16+y}$  (4:3:3:4). Thulium was chosen because it readily formed single-phased compounds (see Ref. 11). Samples from the same pellets were previously studied using x-ray thermogravimetric analysis (TGA) and magnetization measurements.<sup>11</sup> Crystallographic size and the Curie-Weiss susceptibility results show that the Tm dopants are trivalent. The oxygen content versus  $x$  has also been measured by TGA. Several studies on the effect of cationic substitution have been reported previously.<sup>12-14</sup>

Figure 1 shows the values of  $n_H$  (normalized to per Cu ion) for 4:3:3:4 doped with Tm. As in previous studies, the Hall signal is positive (holelike). (The values of  $n_H$  for  $x=0$  are  $\sim 20\%$  larger than the single-crystal result of Takagi *et al.*<sup>15</sup> In an earlier report a lower value for  $n_H$  was obtained for a mixed phase Bi-Sr-Ca-Cu-O sample.<sup>16</sup>) As shown in Fig. 2,  $n_H$  (normalized to the cell volume  $V=440 \text{ \AA}^3$ ) falls linearly with increasing  $x$ , intersecting the  $x$  axis at  $x=1.37$ . Near  $x=0.1$ ,  $n_H$  shows an interesting cusp which is similar to that observed in Ni-doped 1:2:3. The magnitude of  $n_H$  (0.4/Cu ion) in the

$x=0$  sample is also close to the hole density 0.5/Cu(2) inferred<sup>17</sup> for 1:2:3. We have also measured the resistivity ( $\rho$ ) vs  $T$  for all the Hall samples. Samples with  $x$  between 0.0 and 1.0 are metallic, with  $\rho$  falling in the range of 1-10 m $\Omega$  cm. The samples with  $x=1.5$  and 2.0 are approximately 100 times more resistive. Their resistivity is weakly  $T$  dependent above 150 K, but increases strongly below 100 K (in agreement with Ref. 11). For comparison, the variation of  $\rho$  vs  $x$  at 150 K is also shown in Fig. 2. The results show that as the chemical potential  $\mu$  is raised (by increasing  $x$ ), a relatively sharp metal-insulator transition occurs near  $x=1.4$ . Together, the two transport quantities show that transition is associated with a depletion of itinerant carriers.

The linear decrease of the Hall density  $n_H$  is reminiscent of the situation<sup>5</sup> in  $\text{La}_{2-x}\text{Sr}_x\text{CuO}_4$  where  $n_H$  decreases linearly with decreasing  $x$  (Sr content) for  $x$  below

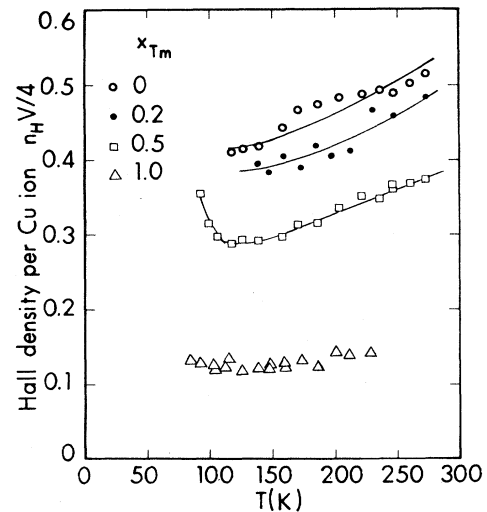


FIG. 1. Temperature dependence of the Hall carrier density per Cu ion,  $n_H V/4$  ( $V=440 \text{ \AA}^3$ ) for various  $x$  in  $\text{Bi}_4\text{Sr}_3\text{Ca}_{3-x}\text{Tm}_x\text{Cu}_4\text{O}_{16+y}$ . The sharp upturn near 120 K in the  $x=0.5$  sample may be caused by partial shorting of the Hall contacts due to superconducting fluctuations.

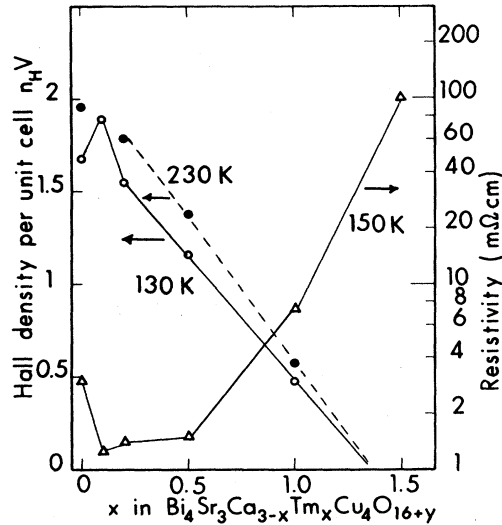


FIG. 2. The variation of the  $n_H V$  (number of carriers per unit cell) in 4:3:3:4 with  $x$  at two temperatures: 130 K (open circles) and 230 K (filled circles). Note the decrease of the slope  $d(n_H V)/dx$  as  $T$  decreases. Extrapolation of  $n_H V$  locates the Mott-Hubbard gap edge at  $x=1.37$ . The polycrystalline resistivity  $\rho$  at 150 K (open triangles, plotted on log scale) increases almost by 100 between  $x=0.5$  and 1.5.

0.15. This behavior provides strong evidence that the 4:3:3:4 compounds are in close proximity to a Mott-Hubbard insulating regime, in marked contrast to band-structure predictions. In the band structure reported by Mattheiss and Hamann<sup>9</sup> (MH) and by Herman, Kasowski, and Hsu<sup>10</sup> (HKH), the Fermi level is intersected by the two subbands formed from the familiar Cu 3d-O 2p and the Bi 6p-O 2p states. MH estimate the total carrier density to be  $8.8 \times 10^{21} \text{ cm}^{-3}$ , with 10% of the carriers in the Bi 6p-O 2p subband. Very low charge concentration is found at the Ca sites. Because of the overlap of the two subbands, the density of states (DOS) shows no gap between  $\mu$  and the Bi 6p manifold which extends 4 eV above  $\mu$ . We first analyze the Hall data using the  $U=0$  band structure. Increasing  $x$  (Tm) from 0 to 1.5 in 4:3:3:4 implies that the electron population on the CuO<sub>2</sub> planes is increased by 0.4 per Cu ion. Assuming a bandwidth  $W$  of 3 eV for the Cu 3d-O 2p band,<sup>9</sup> we infer that  $\mu$  is raised by  $W\delta/2 \sim 600$  mV. It is clear that within the  $U=0$  picture such a relatively small shift in  $\mu$  cannot result in insulating behavior. From the 3-eV width of the 3d-2p subband, and the strong overlap with the Bi 6p-O 2p subband, we would predict that  $n_H$  should remain relatively unchanged as  $\mu$  is raised by  $W\delta/2$ . In contrast, we observe a rapid linear decrease of  $n_H$  to very small densities. Thus, the Hall data provide strong evidence for a large gap approximately  $W\delta/2$  in energy above  $\mu$  in the 85-K system. The 100-fold jump in the resistivity between  $x=0.5$  and 1.5 is also consistent with the existence of the Mott-Hubbard gap. (Results for  $R_H$  and  $\rho$  in the 4:4:2:4 phase doped with Tm, with  $x=0.5, 1.0$ , and 1.5 are broadly similar to the above.)

In analogy with the case of  $\text{La}_{2-x}\text{Sr}_x\text{CuO}_4$  ( $x < 0.15$ ),

we argue that the ground state of the Bi 2:2:1:2 system is a large- $U$  Hubbard system. The Cu ions are all in the  $3d^9$  state. Due to strong correlations, charge fluctuations are strongly suppressed;<sup>18</sup> the *strictly* stoichiometric compound  $\text{Bi}_2(\text{Sr}, \text{Ca})_3\text{Cu}_2\text{O}_8$  (without the Bi-O plane modulation) should be a good Mott-Hubbard insulator, despite the fact that  $\mu$  is close to midband in the  $U=0$  band structure. However, in the as-grown 4:3:3:4 compound (the  $x=0$  sample) there already exists a significant density of itinerant holes, i.e.,  $\mu$  is lower than the Mott-Hubbard gap edge (see below). Nominally, the holes occupy states with mostly O 2p character.<sup>19</sup> Recent theoretical models<sup>20</sup> identify the carriers as a *singlet* bound state formed from a symmetric combination of O 2p $\sigma$  and the Cu  $3d_{x^2-y^2}$ , referred to as  $d^9 \underline{L}$  (or formal  $\text{Cu}^{3+}$ ). Substitution of  $\text{Ca}^{2+}$  with trivalent Tm raises the chemical potential. The ligand-hole population is steadily decreased as  $x$  increases until near  $x=1.4$ , the population is driven to zero, and  $\mu$  is located within the Mott-Hubbard gap. From the resistivity data the system becomes insulating for  $x > 1.4$ . The similarity with the case<sup>5</sup> of decreasing the Sr content in 2:1:4 ( $x < 0.15$ ) is quite close.

The argument above not only implies that the Cu 3d-O 2p subband is split at midband by the Mott-Hubbard gap, but also requires that the Bi 6p-O 2p subband *not* contain any current carrying states near  $\mu$ . (Otherwise, neither the linear approach of  $n_H$  to zero nor the insulating behavior for  $x > 0$  would be observed.) This suggests that either the minimum of the Bi 6p-O 2p subband is situated much higher than shown by the band-structure calculations, or that the states in the Bi-O plane are *strongly* localized. In this case the Bi-O planes act as an electron reservoir similar to the Cu(1) chains<sup>6</sup> in 1:2:3. As  $x$  increases, the fraction of holes in the Cu-O planes is decreased while the localized holes in the Bi-O planes increase. However, the latter do not affect the Hall signal, which measures only the itinerant carriers. A discussion of whether the Bi 6p-O 2p subband intersects  $\mu$  has also been given by Sleight.<sup>21</sup>

The variation of  $T_c$  with Tm content (shown in Fig. 3) shows the surprising nonlinear trend previously reported in Ref. 11. Rather than decreasing linearly with  $x$ ,  $T_c$  shows a slight initial increase ( $\sim 4$  K) and then stays roughly constant until  $x$  exceeds 0.5. Beyond 0.5,  $T_c$  decreases rapidly, becoming zero in the  $x=1.5$  sample. On the basis of the Hall data in the range  $0 < x < 0.5$ , we adopt the viewpoint that the plateau in  $T_c$  occurs *despite* a significant change in  $n$  (see Ref. 11 for an alternate view). A similar plateau at 40 K is well known in the 2:1:4 system.<sup>8</sup> Interestingly,  $T_c$  is actually lower (and  $\rho$  higher) in the  $x=0$  sample compared with the  $x=0.1$  and 0.2 samples, i.e., carrier scattering is more severe in the  $x=0$  sample. This is brought out by plotting the polycrystalline Hall mobility  $\mu_H$  ( $=R_H/\rho$ ) vs  $x$  in Fig. 3 (filled circles). The rather severe reduction in  $\mu_H$  as  $x$  approaches 0 suggests that the carriers in undoped 4:3:3:4 undergo more scattering than in the lightly doped samples. These results can be accounted for by assuming that the strong incommensurate modulation<sup>22</sup> in the Bi-O planes leads to defects which strongly scatter the carriers in the CuO<sub>2</sub> planes. Substitution of Ca with Tm at the sites between

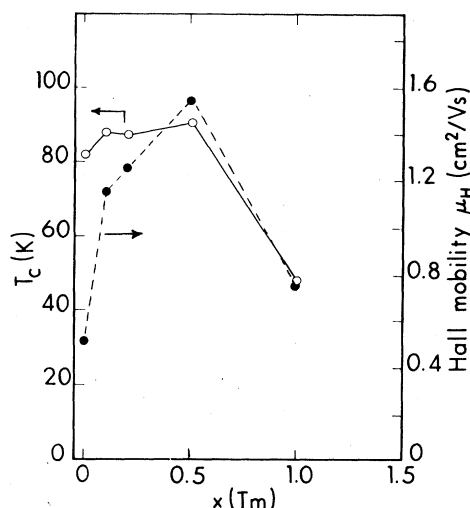


FIG. 3. Variation of the transition temperature  $T_c$  vs  $x$  (open circles) compared with the polycrystalline Hall mobility  $\mu_H$  at 150 K (filled circles) for Tm-doped 4:3:3:4 ( $T_c$  for the  $x=1.5$  and 2.0 samples is zero.) The decrease in both quantities as  $x$  approaches 0 suggests increased lattice-defect scattering in the  $x=0$  sample.

the  $\text{CuO}_2$  planes apparently helps to relieve the strain and reduce the defect density. This leads to an improvement in  $\mu_H$  and a slight enhancement of  $T_c$ . At large  $x$ , the improvement in  $\mu_H$  entails the cost of carrier reduction (as shown in Fig. 2) so that  $T_c$  eventually decreases. The nonmonotonic variation of  $T_c$  with  $x$  indicates that in addition to  $n$ , scattering mechanisms acting within the  $\text{CuO}_2$  planes may have a significant inhibitive effect on  $T_c$  in the high- $T_c$  oxides, as suggested by the Ni-doping studies<sup>17,23</sup> on 1:2:3 and 2:1:4.

In Ref. 23, which analyzes the  $T$  dependence of  $n_H$  in 2:1:4 and 1:2:3, it was shown that whenever  $T_c$  is suppressed by creating in-plane disorder (substituting Cu with Ni), or by depleting  $n$  (substituting with Co), the slope  $dn_H/dT$  is systematically suppressed as well. The results in Fig. 1 show that a similar trend also prevails for the Bi system. Whereas in the  $x=0, 0.2, 0.5$  samples  $n_H$  increases with  $T$  (although not as strongly as in 1:2:3), the  $T$  dependence of  $n_H$  is negligible in the  $x=1$  sample where  $T_c$  has been depressed to 50 K. The decrease in the  $T$  dependence of  $n_H$  (as  $T_c$  is suppressed) results in the characteristic "converging" pattern of the  $n_H$  vs  $x$  curves at different  $T$ 's in Fig. 2. Such converging profiles were previously found<sup>23</sup> in 1:2:3 (doped with Co and Ni) and in Ni doped 2:1:4. In Fig. 2, the slope  $d(n_H V)/dx$  at large  $x$

systematically changes from  $-1.60$  (at 230 K) to  $-1.30$  (at 130 K). This strongly suggests that the slope may approach the value  $-1.0$  (consistent with each Tm donating one excess electron to the  $\text{CuO}_2$  planes) at sufficiently low  $T$ .

We next consider the source of the holes in the  $x=0$  sample. Direct charge balance in  $\text{Bi}_4\text{Sr}_3\text{Ca}_{3-x}\text{Tm}_x\text{Cu}_4\text{O}_{16+y}$  implies that the filling factor  $\delta$  equals  $(2y-x)/4$ . For the  $x=0$  sample, TGA measurements<sup>11</sup> yield  $y=0.25-0.30$ , corresponding to  $\delta_{\text{TGA}}=0.125-0.15$ . A higher value for  $y=0.42$  (implying  $\delta=0.21$ ) has been obtained in another study<sup>24</sup> which compares Bi 2:2:1:2 with the new isostructural compound  $\text{Bi}_{10}\text{Sr}_{15}\text{Fe}_{10}\text{O}_{46}$ . These numbers are significantly lower than the  $\delta(0.4)$  derived from the Hall data. Although further work is required to resolve the discrepancy, we note that the linear extrapolation of  $n_H$  to zero implies that the Mott-Hubbard edge is at  $x=1.4$  which is close to the value 1.6 computed from  $4\delta$ , i.e., the Hall data appear to be tracking the carrier population fairly closely. The charge balance estimate is sensitive to very slight Bi or Sr deficiencies. (For example, if 1 out of 16 Bi atoms is missing in the  $x=0$  sample, our value for  $\delta$  would be consistent with the value of  $y=0.42$  given in Ref. 24.) In view of the incommensurate modulation of the Bi-O plane<sup>21</sup> such slight deficiencies in Bi or Sr cannot be excluded. The TGA results<sup>11</sup> also show that  $y$  increases roughly linearly from 0.25 (at  $x=0$ ) at  $\sim 1.2$  (at  $x=2.0$ ). The large change in anion charge is also difficult to reconcile with the Hall data.

In summary, Hall measurements on Bi 2:2:1:2 show that the hole density (0.4/Cu) is close to that found<sup>17</sup> in 1:2:3 [0.5/Cu(2)]. The removal of these holes by Tm doping drives the system insulating, in sharp contrast to band-structure predictions. Thus, we believe that Bi 2:2:1:2 is a strongly correlated Mott-Hubbard system, with a behavior remarkably similar to 2:1:4. The significant density of holes in the undoped compound is possibly due to oxygen excess or deficiency in Sr and Bi. Rather than being linear in  $n$ ,  $T_c$  vs  $x$  exhibits a broad plateau peaking at 85 K. The variation of the Hall mobility with  $x$  suggests that the undoped compound may have severe lattice strain. We also discussed the implications for the existence of a large overlap at  $\mu$  between subbands formed from  $\text{Cu } 3d\text{-O } 2p$  and  $\text{Bi } 6p\text{-O } 2p$  states.

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